March 19, 2015 ~ NIL Industrial Day (part 1)

10:30 Registration / Commercial Exhibition
11:00 Welcome (A. Schleunitz)

Session 1: 3D patterning methods and additive manufacturing
Session Chair: M. Mühlberger

11:10 - S. Westenhöfer, Heptagon Micro Optics
   “Novel applications for micro-optical elements in mobile devices”
11:30 - S. Diez, Heidelberg Instruments GmbH
   “Advanced Grayscale Lithography”
11:50 - Ch. Teissl, Swarovski
   “Sub-Micron Structuring of Surfaces - the Swarovski Perspective”
12:10 - L. Häusler, PROFACTOR
   “Challenges for Nanoimprinting for Additive Manufacturing and on Complex Surfaces”
12:30 - L. Jacot-Descombes, micro resist technology
   “Combining UV-NIL and inkjet printing for fabrication 3D optical components”
12:40 - Y. Suto, Soken Chemicals & Engineering Co., Ltd.
   “Development of Ultra Large Area Mold by Step & Repeat Method”
13:00 - Break

Session 2: Industrial nanopatterning solutions
Session Chair: G. Grützner

13:35 - M. Tormen, ThunderNIL srl
   “Ultrafast NIL: an opportunity for present and future industrial nanotech applications”
13:55 - R. van der Waal, Philips Innovation Services
   “Industrialization of custom SCIL-based process flows”
14:15 - S. Landis, CEA-LETI
   “NIL for industrial early adopters – the INSPIRE project”
14:35 - E. Storace, SUSS MicroTec
   “SUSS SMILE Technology – A Large Area Imprint solution for patterning of micro and nano features”
14:55 - L. Lindvold, Stensborg A/S
   „Life in the Nip - HololmPrint revisited“
15:15 - M. Guttmann, Karlsruhe Institute of Technology
   “Novel process chain for the fabrication of nanostructured mold inserts made in or on steel”
15:50 - Break

Session 3: Industrial nanopatterning production
Session Chair: S. Landis

16:20 - M. Thesen, micro resist technology
   “Industrial application of soft photo-NIL – A versatile match of resists and stamp materials”
16:30 - B. Böhm, OSRAM
   “LED surface roughening by NIL for volume manufacturing at OSRAM”
16:50 - T. Glinsner, EV Group
   “NIL for Industrial Applications”
17:10 - S. Bowen, Illumina
   “Nanotechnology for a Genomic Revolution”
17:30 - R. Price, PragmatIC Printing Ltd
   “Towards sub-micron flexible integrated circuits”
17:50 - P. Lundström, Obducat AB
   “NIL enables cost reduction in industrial nano patterning”
18:10 - Closing remarks
19:00 - Dinner
March 20, 2015 ~ NIL Industrial Day (part 2)

09:00  Welcome / Commercial Exhibition

Session 4: Etching of nanopattern – state-of-the-art and challenges
Session Chair: A. Schleunitz

09:10 - C. Pinnow, Sentech Instruments GmbH
"Advanced ICP based micro- and nanopatterning for industrial and R&D applications"

09:30 - M. Cooke, Oxford Instruments plc
"Challenges of pattern transfer in the deep nanoscale"

09:50 - F.C. Smits, Roth & Rau B.V.
"Industrial inkjet printing and etching - challenges and solutions"

10:10 - N. Gadegaard, University of Glasgow
"Nanopatterned plastics for medical applications"

10:30 - V. Cadarso, Paul Scherrer Institute
"Combining silicon micro- and nanostructures by means of cryoetching"

10:50 - Break

Session 5: Future vision of NIL
Session Chair: H. Schift

11:20 - C. Pina-Hernandez, aBeam Technologies Inc.
"Imprinting of High Refractive Index Materials for Optical Applications"

11:40 - J.J. Lee, Korea Institute of Machinery and Materials
"Multi-functional Nanoimprint Lithography Technology and Its Applications"

12:00 - B. H. Kim, University of Massachusetts
"Development of roll-to-roll molding fabrication for 3D layered metamaterial structures"

12:20 - T. Tachtsidis, nanotypos
"Roll-to-Roll nanoimprint lithography manufacturing"

12:40 - M. Rommel, Fraunhofer IISB
"UV NIL R&D at Fraunhofer IISB - past examples and future trends"

13:00 - I. Bergmair Sony DADC Austria AG, M. Mühlberger, PROFACTOR
"Opportunities for Nanoimprinting – the Austrian Perspective"

13:20 - Closing remarks and lunch (A. Schleunitz)

14:00 - End

Sponsors:  micro resist technology
Exhibitors:  EVG  PROFACCTOR
                     Soken
                     SSU+Microtec
                     SENTECH
                     SEMICONDUCTOR &  NIL
                     High Technology Trading & Liaison

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Code: „NIL-Industrial Day“
Contact: Anja Wehnert

Local organizer:
Gabi Grützner, Dr. Arne Schleunitz
micro resist technology GmbH
Köpenicker Straße 325
12555 Berlin - Germany
www.microresist.de

Commercial exhibition:
Day 1 - 10:30 - 19:00
Day 2 - 09:00 - 14:00

Participation fee
(incl. refreshments and dinner)
245 EUR (excl. 19% VAT)
You will receive a confirmation of registration and invoice
Speakers free